Tool ID: 201 Tool Location: 107

Equipment Information Sheet

PT72 Etcher

Manager:Christopher Alpha607-254-4913Calls to staff phones will be automatically forwarded to their cell phones during accessible hours. At other times leave a message or send them an email.Backup:Tom Pennell607-254-4309

SAFETY

• No unusual hazards during normal operation

USAGE RESTRICTIONS

• No buddy system restrictions imposed on normal operation

SCHEDULING/SIGN-UP RESTRICTIONS

• Maximum 2 hour block

• Maximum 2 reservations in advance at any time

Minimum Tool Time: 15 minutes

MATERIALS COMPATIBILITY CATEGORY

Tool Category 4: Glass and Metal Categories	
Allowed	Not Allowed
Tool category 1/1E, 2, and 3 materials	
Silicon Based Substrates and Films	No CNF Class A metals
III/V compound Semiconductors	No Exposed CNF Group B metals- metals can be buried/covered with staff approval
Glass Substrates	Cannot be used as an etch stop
PECVD and ALD Films	
Buried Class B Metals with approval	
Organic/Bio Materials prepped w/o Salt Buffers	
Cured organics and baked Photoresist	No High Vapor pressure materials

High Vapor Pressure Metals and Compounds are materials that have a vapor pressure above 1e-6 Torr at 400 C.

Additional Material Restrictions and Exceptions

- No gold or silver etching
- No high vapor pressure materials (lead indium, ITO)
- No microscope slides

Last Updated: 12/20/2022